



ABSTRACT

~~METHOD FOR MAGNETRON SPUTTERING~~

- 5 The invention relates to a method for enhancing erosion uniformity on the sputtering surface of a magnetron cathodic sputtering target. The invention is characterised in that it consists in adding to said target intended to be coupled to a magnetron maintained fixed as compared to this target, at least one ferromagnetic piece for complete or partial insertion into said target or by juxtaposition thereto, so
- 10 as to bring about, at the entire sputtering surface, a curvature reduction of the magnetic induction lines generated by the magnetron.